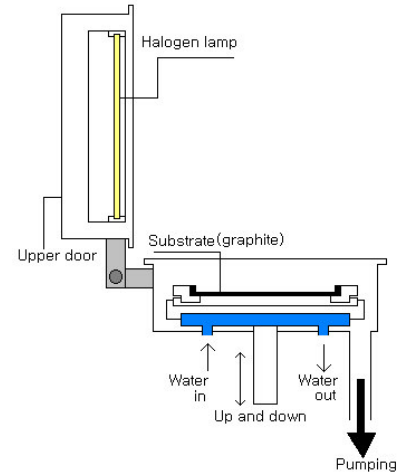


ATS-Rapid Heating Series Vacuum Heating System for Voids Free

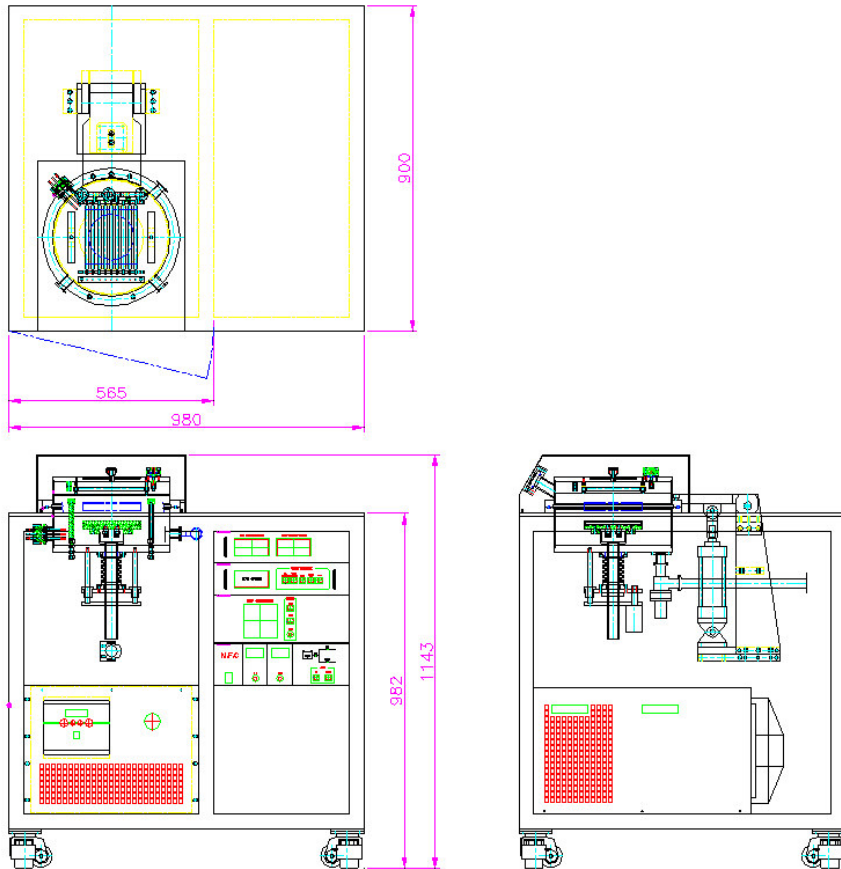


Schematic diagram of vacuum heating system

Special Features

- ◆ Soldering and rapid thermal annealing under vacuum
 - ◆ High heating rate using halogen lamp (Max. Temp. 800°C on request)
 - ◆ Process recipes based on customer request
 - ◆ Automatically controlled by PC
 - ◆ Rapid ramping :
 - >200°C/min on the top of graphite plate heated by quartz lamp
 - ◆ Ramp down :
 - ~100°C/min with graphite plate and
 - <20°C/s without graphite plate
 - ◆ Ramp rate is precisely controlled
 - ◆ Heated area: 6 inch
 - ◆ Substrate cooling by N₂ gas or water according to application process
 - ◆ Longitudinally movable substrate holder
- ◆ Up to 6 gas lines, 2 gas lines standard
 - ◆ Wafer capacity
 - 1 × 6"
 - ◆ Average throughput
 - Up to 18,000 wafers per year
 - ◆ Dimension : 990L × 1,143H × 900W (mm³)
 - ◆ Customer specific processes or option on request
 - ◆ Others
 - Power :220V, 3 phase, 50A
 - Gas : N₂ / Ar
 - Susceptor material : stainless steel 304
 - Heater : halogen lamp
 - Pump : rotary (600l/min)
 - turbomolecular pump (optional, 600l/sec)
 - ◆ Applications
 - Wafer bump reflow and SMD soldering
 - Photo sensitive materials curing
 - Rapid thermal annealing and alloying
 - Package lid sealing

◇ Layout



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